

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Satoru Okamoto                      Art Unit : Unknown  
Serial No. : New Application                      Examiner : Unknown  
Filed : October 22, 2003  
Title : METHOD FOR CLEANING PLASMA ETCHING APPARATUS, METHOD  
FOR PLASMA ETCHING, AND METHOD FOR MANUFACTURING  
SEMICONDUCTOR DEVICE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT**

Applicant submits the reference listed on the attached form PTO-1449.

This statement is being filed with the application. No fees are believed due. Please apply any charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: October 22, 2003

  
\_\_\_\_\_  
John F. Hayden  
Reg. No. 37,640

Fish & Richardson P.C.  
1425 K Street, N.W.  
11th Floor  
Washington, DC 20005-3500  
Telephone: (202) 783-5070  
Facsimile: (202) 783-2331

Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 12732-170001	Application No. New Application
	Applicant Satoru Okamoto		
	Filing Date October 22, 2003	Group Art Unit Unknown	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AQ	Kawada; "An <i>In Situ</i> Analysis of Residue Deposited on an Etching Chamber's Surface"; <i>Plasma Science Symposium 2001/The 18<sup>th</sup> Symposium on Plasma Processing Proceedings</i> ; pp. 241-242; 2001
	AR	
	AS	
	AT	

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	